HOLDING CHAMBER FOR FACE MASK

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See application file for complete search history.

References Cited

U.S. PATENT DOCUMENTS

D511,210 S * 11/2005 Cardona Burrull D24/110.5

* cited by examiner

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CLAIM

The ornamental design for a holding chamber for face mask, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view showing our new design;
FIG. 2 is a front elevational view thereof;
FIG. 3 is a rear elevational view thereof;
FIG. 4 is a left side elevational view thereof;
FIG. 5 is a right side elevational view thereof;
FIG. 6 is a top plan view thereof; and,
FIG. 7 is a bottom plan view thereof.
The broken lines illustrate portions of the holding chamber for face mask which form no part of the claimed design.

1 Claim, 4 Drawing Sheets